

# PATENT ABSTRACTS OF JAPAN

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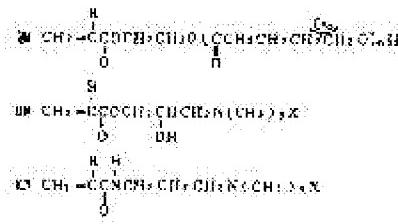
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## (54) PHOTOSENSITIVE RESIN COMPOSITION

### (57)Abstract:

PURPOSE: To obtain the titled composition giving a less colored and transparent relief pattern and having a good dyeability by photosensitizing a copolymer contg. a specific monomer and a specific monomer having a structure of a quaternary ammonium salt as a main component with a bisazide compd.

CONSTITUTION: The titled composition is constituted by incorporating the bisazide compd. to the copolymer composed of the monomer contg. a hydroxy group shown by formula I and the monomer having the structure of the quaternary ammonium salt shown by formula II or III as the main component. In formula I, R is H atom or CH<sub>3</sub> group, X is an acidic group, (n) is an integer of 1W4. The bisazide compd. is used as a photocrosslinking agent, and is exemplified by 4,4'-diazido stilbene-2,2'-disulfonic acid sodium salt, 2,6-bis(4'-azido benzal)methylcyclohexanone-2',2'-disulfonic acid sodium salt, etc., and is incorporated 1W10wt% per the copolymer. Thus, less colored and transparent relief pattern which is formed by exposing and developing, it obtd., and the titled composition not affects



adverse effect to a color after coloring.